



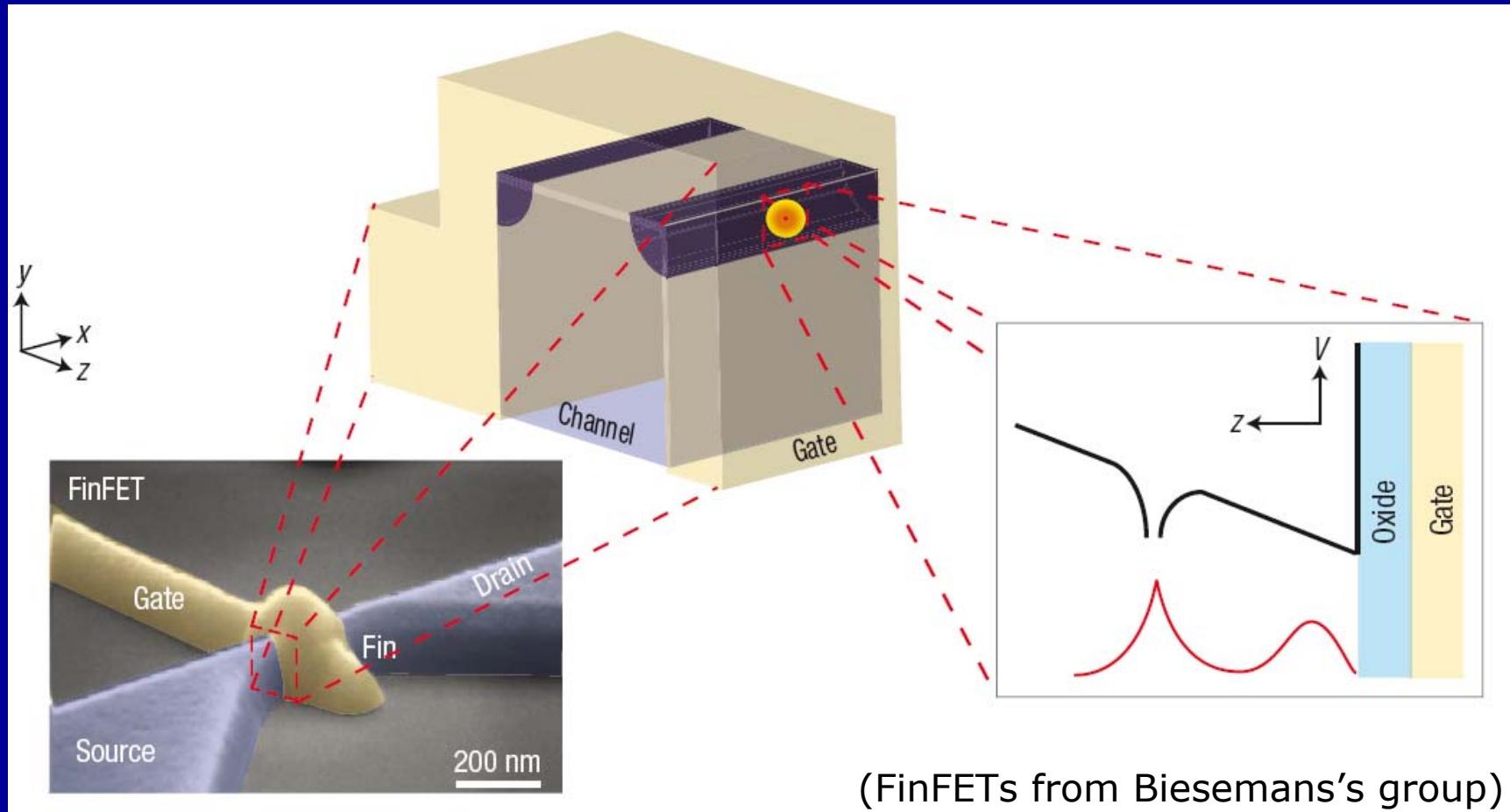
Heterointerface effects on the charging energy of shallow D⁻ ground state in silicon: the role of dielectric mismatch.

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Ref: M.J. Calderón, J. Verduijn, G.P. Lansbergen,
G.C. Tettamanzi, S. Rogge, B. Koiller,
Phys. Rev. B 82, 075317 (2010)

MOTIVATION

FinFET: single donor detection device



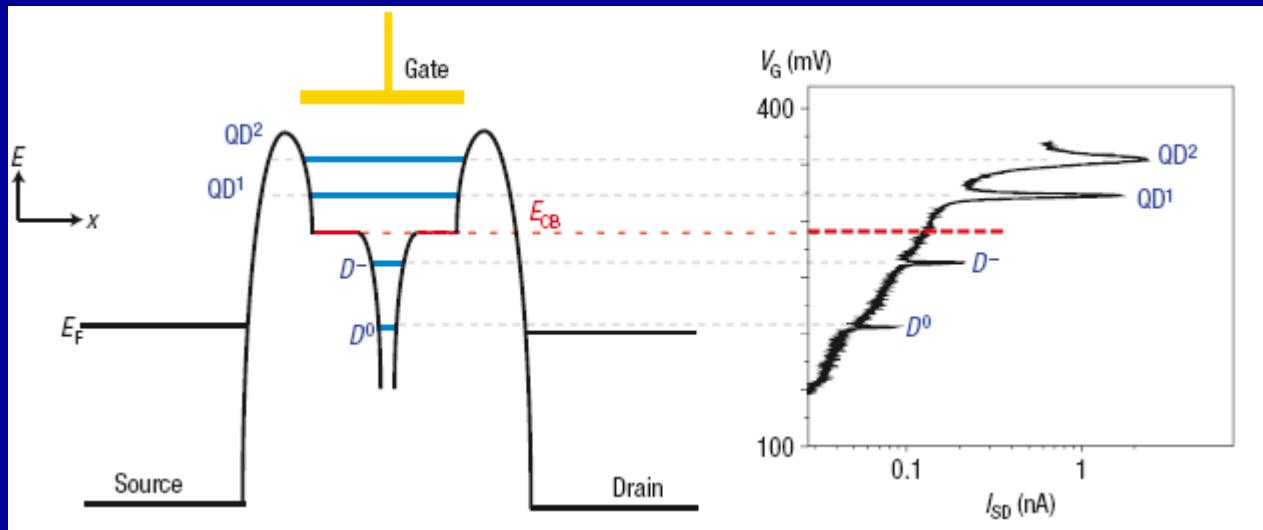
(FinFETs from Biesemans's group)

Arsenic donors may diffuse from source or drain to the channel

Sellier et al, PRL (2006)
Lansbergen et al, Nat. Phys. 4, 656 (2008)

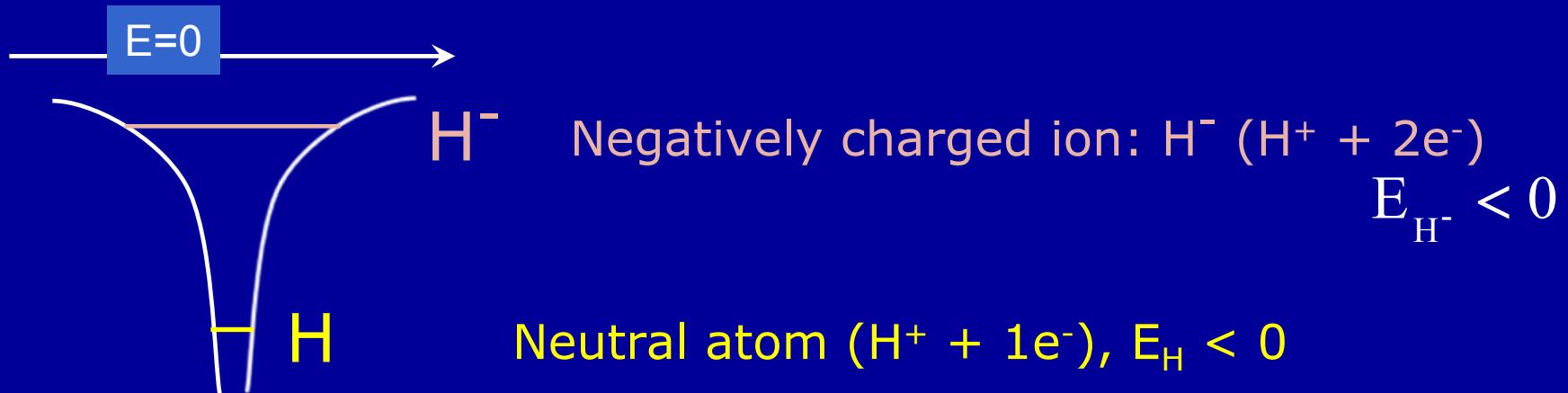
MOTIVATION

FinFET: transport spectroscopy



- ✓ Two resonances, corresponding to the 2 possible donor bound states (D^0 and D^-) are observed below the conduction band.

Hydrogen bound charge states

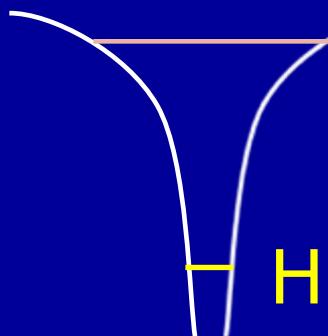


$$U_{\text{coul}} = -\frac{e^2}{r}$$

Binding energy for H^-

$$E_B^{H^-} = E_H - E_{H^-} (> 0)$$

Hydrogen bound charge states



H^- Negatively charged ion: $H^- (H^+ + 2e^-)$

Neutral atom ($H^+ + 1e^-$)

Non-interacting e^- energy for H^-

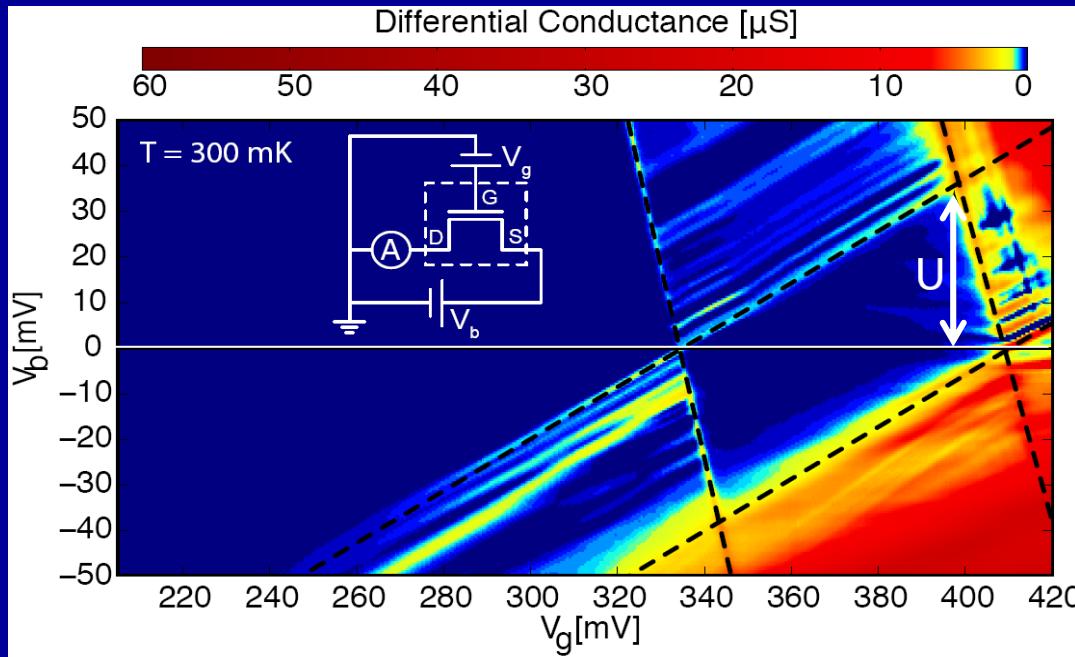
$$E_{H^-} = 2E_H$$

Charging energy:
 $\sim e^- \leftrightarrow e^-$ repulsion

$$E_{H^-} = 2E_H + U \Rightarrow U = E_{H^-} - 2E_H > 0$$

Stability diagram Fin FET Experiments

Charging energy
 $U = 36 \pm 1$ meV



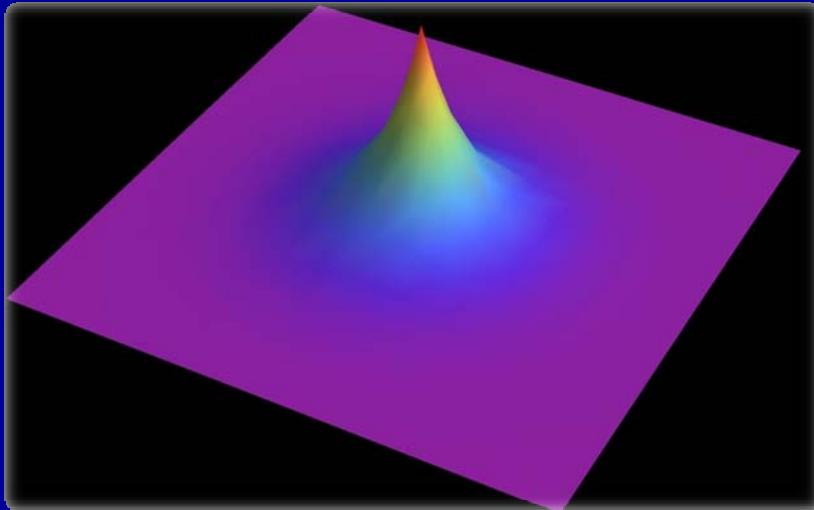
Similar values found in other samples ($U \sim 28-36$ meV)
However, U_{As} in bulk Si ~ 52 meV

Where does the reduction in U come from?
We investigate the role of the dielectric mismatch at the interface.

Neutral hydrogen atom H⁰

Hamiltonian for 1 electron

$$h(r) = -\nabla^2 - \frac{2}{r}$$



Ground state

$$\phi_{1s}(r, a) = \frac{1}{\sqrt{\pi a^3}} e^{-r/a}$$

with $a = 1 a_B$ and $E_H = -1 \text{ Ry}$

Atomic units are
adopted here

$$a_B = \frac{\hbar^2}{m_e e^2} = 0.5 \text{ \AA}^\circ$$

$$\text{Ry} = \frac{m_e e^4}{2 \hbar^2} = 13.6 \text{ eV}$$

Negative hydrogen ion H⁻

Proton + e- + e-

Hamiltonian for 2 electrons

$$H_{bulk} = h(r_1) + h(r_2) + \frac{2}{|\vec{r}_1 - \vec{r}_2|}$$

Variational trial ground state function (spin singlet)

$$|1s, 1s, s\rangle = [\phi_{1s}(r_1, a) \phi_{1s}(r_2, b) + \phi_{1s}(r_1, b) \phi_{1s}(r_2, a)] (|\uparrow\downarrow\rangle - |\downarrow\uparrow\rangle)$$

Results

$$E^{H^-} = -1.027 \text{ Ry} \Rightarrow E_B^{H^-} = 0.027 \text{ Ry}, \quad U = 0.973 \text{ Ry}$$

$a = 0.963 a_B$ (effective Bohr radius of inner orbital)

$b = 3.534 a_B$ (effective Bohr radius of outer orbital)

} Variational

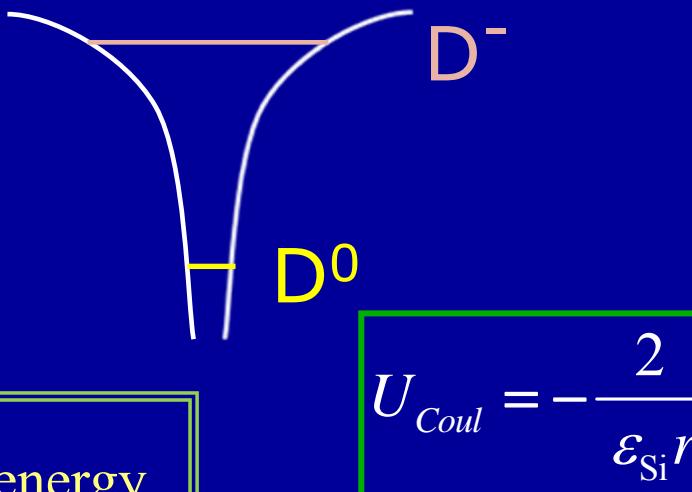
Shallow donors in bulk Si within hydrogenic analogy

$$Ry \rightarrow Ry^* = \frac{m^* e^4}{2 \varepsilon_{\text{Si}}^2 \hbar^2} = 31.2 \text{ meV}$$

$$a_B \rightarrow a^* = \frac{\hbar^2 \varepsilon_{\text{Si}}}{m^* e^2} = 2.14 \text{ nm}$$

$$\left. \begin{array}{l} E^{D^0} = -1Ry^* \\ E^{D^-} = -1.027Ry^* \end{array} \right\} E_B^{D^-} = 0.027Ry^* \rightarrow \text{binding energy}$$

$$U = 0.973Ry^* \rightarrow \text{charging energy}$$



Theoretical bulk values

Experimental bulk values

	D (Ry*)	D (meV)
$E_B^{D^0}$	1	31.2
$E_B^{D^-}$	0.027	0.84
U	0.973	30.36

	P	As
$E_B^{D^0}(\text{meV})$	45	54
$E_B^{D^-}(\text{meV})$	1.7	2.05
U(meV)	43.3	51.95

Approximations

- ✓ Isotropic mass: $m^* \sim 0.3 m_e$
- ✓ Single valley
- ✓ Flat band (no electric field)
- ✓ Simple variational wave-function

Not included:

Mass anisotropy
 $(m_{\perp} = 0.191 m_e, m_{||} = 0.916 m_e)$

Multivalley conduction band
structure



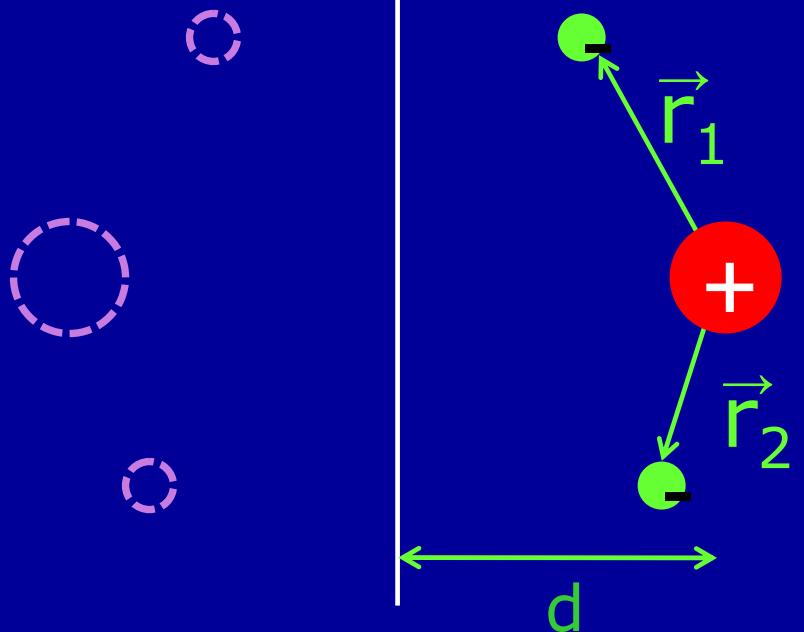
enhancement of $E_B^{D^0}$ and $E_B^{D^-}$
Inoue et al PRB 77, 125213 (2008)
Larsen PRB 23, 5521 (1981)

A more complex variational wave-function (Chandrasekar-type)
for D^- increases its binding energy. Hao et al, arXiv:1005.2315

Boundary problem

Image charges

Barrier



Boundary problem

Image charges

$$H_{\text{images}}(r_1, r_2) = -\frac{Q}{2(z_1 + d)} - \frac{Q}{2(z_2 + d)}$$

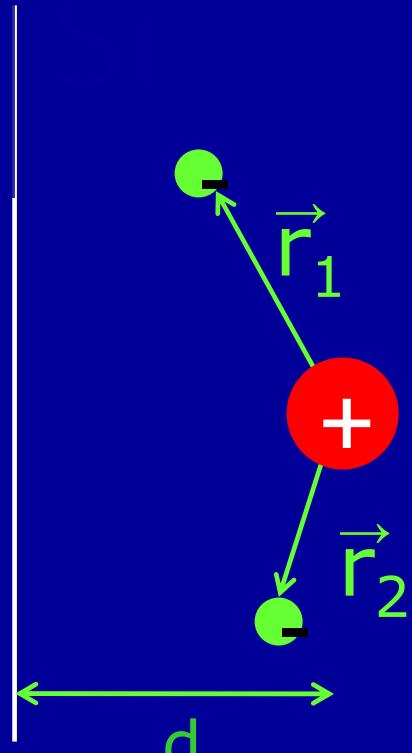
Interaction of each electron with its own image

Interaction of each electron with the donor's image

$$+ \frac{2Q}{\sqrt{x_1^2 + y_1^2 + (z_1 + 2d)^2}} + \frac{2Q}{\sqrt{x_2^2 + y_2^2 + (z_2 + 2d)^2}}$$

$$- \frac{4Q}{\sqrt{(x_1 - x_2)^2 + (y_1 - y_2)^2 + (2d + z_1 + z_2)^2}}$$

Dielectric mismatch parameter



$$Q = \frac{\epsilon_{\text{barrier}} - \epsilon_{\text{Si}}}{\epsilon_{\text{barrier}} + \epsilon_{\text{Si}}}$$

Boundary problem

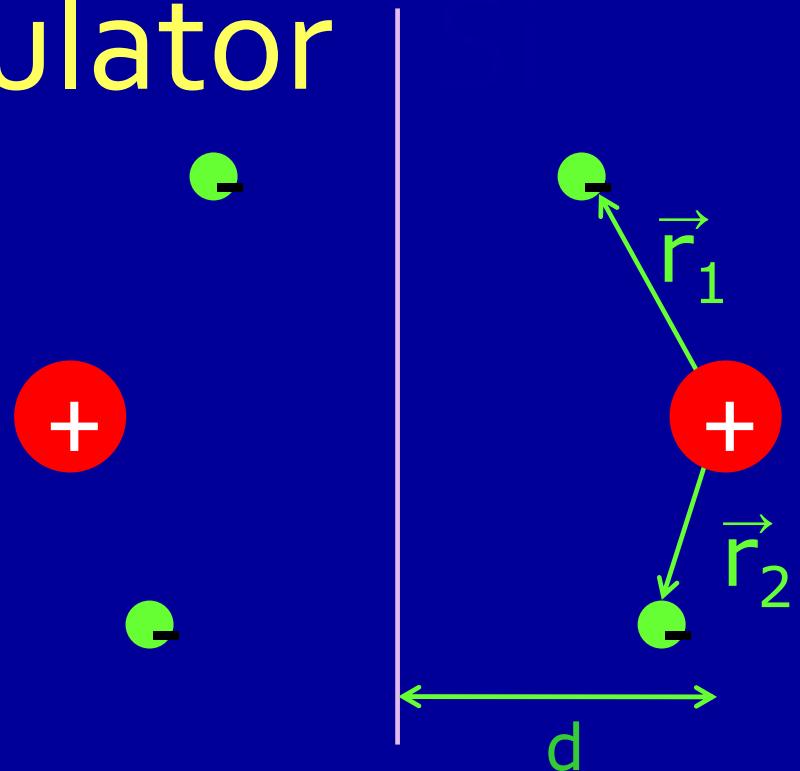
Image charges

$$Q = \frac{\epsilon_{\text{barrier}} - \epsilon_{\text{Si}}}{\epsilon_{\text{barrier}} + \epsilon_{\text{Si}}}$$

Insulator

Ins. barrier $\Rightarrow Q < 0$

Attractive donor image;
repulsive electron images



Note: A rigorous calculation would involve an infinite set of image charges
Hao et al, PRB 80, 035329 (2009).

Boundary problem

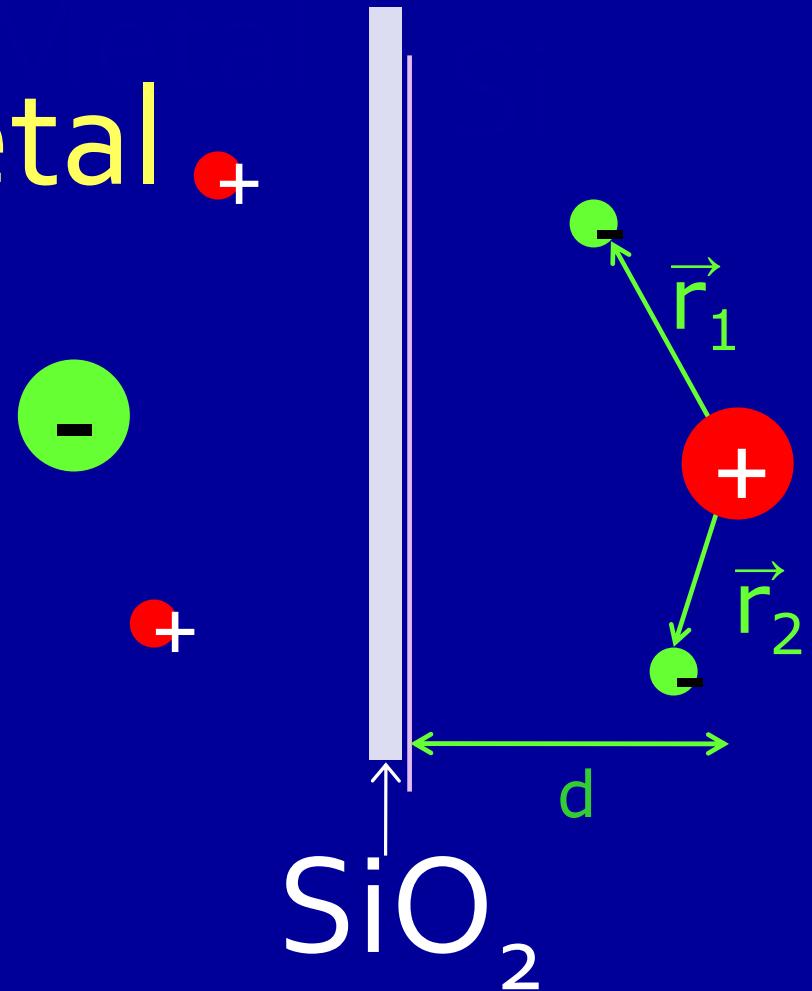
Image charges

$$Q = \frac{\epsilon_{\text{barrier}} - \epsilon_{\text{Si}}}{\epsilon_{\text{barrier}} + \epsilon_{\text{Si}}}$$

Metal +

Thin ins. + metal $\Rightarrow Q > 0$

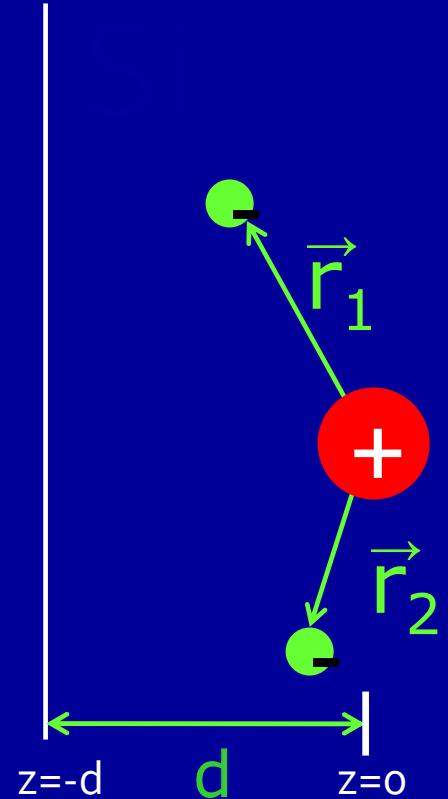
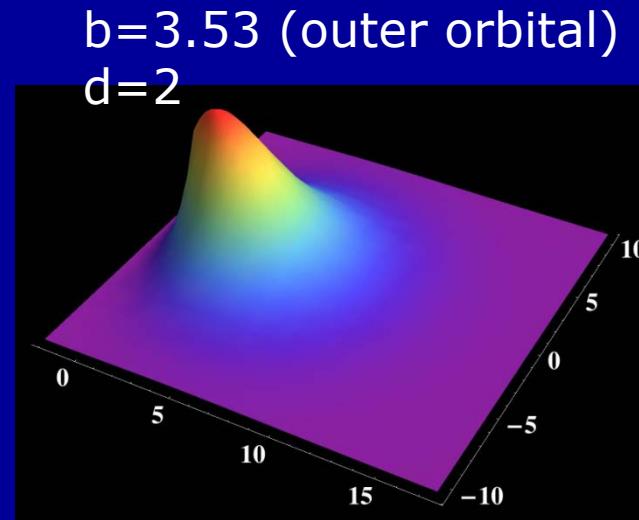
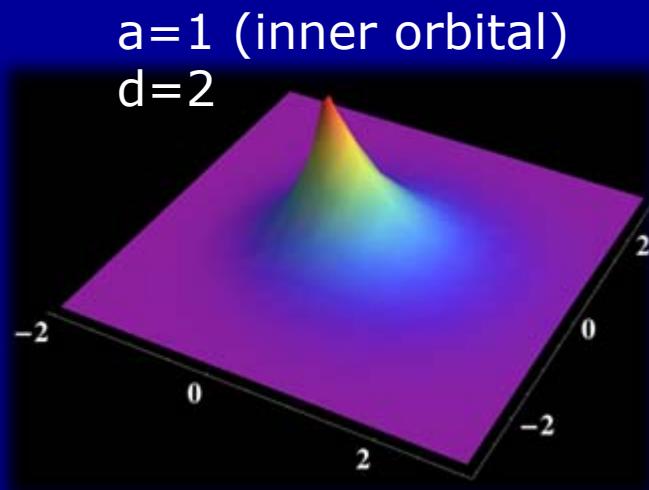
Repulsive donor image;
attractive electron images



Note: A rigorous calculation would involve an infinite set of image charges
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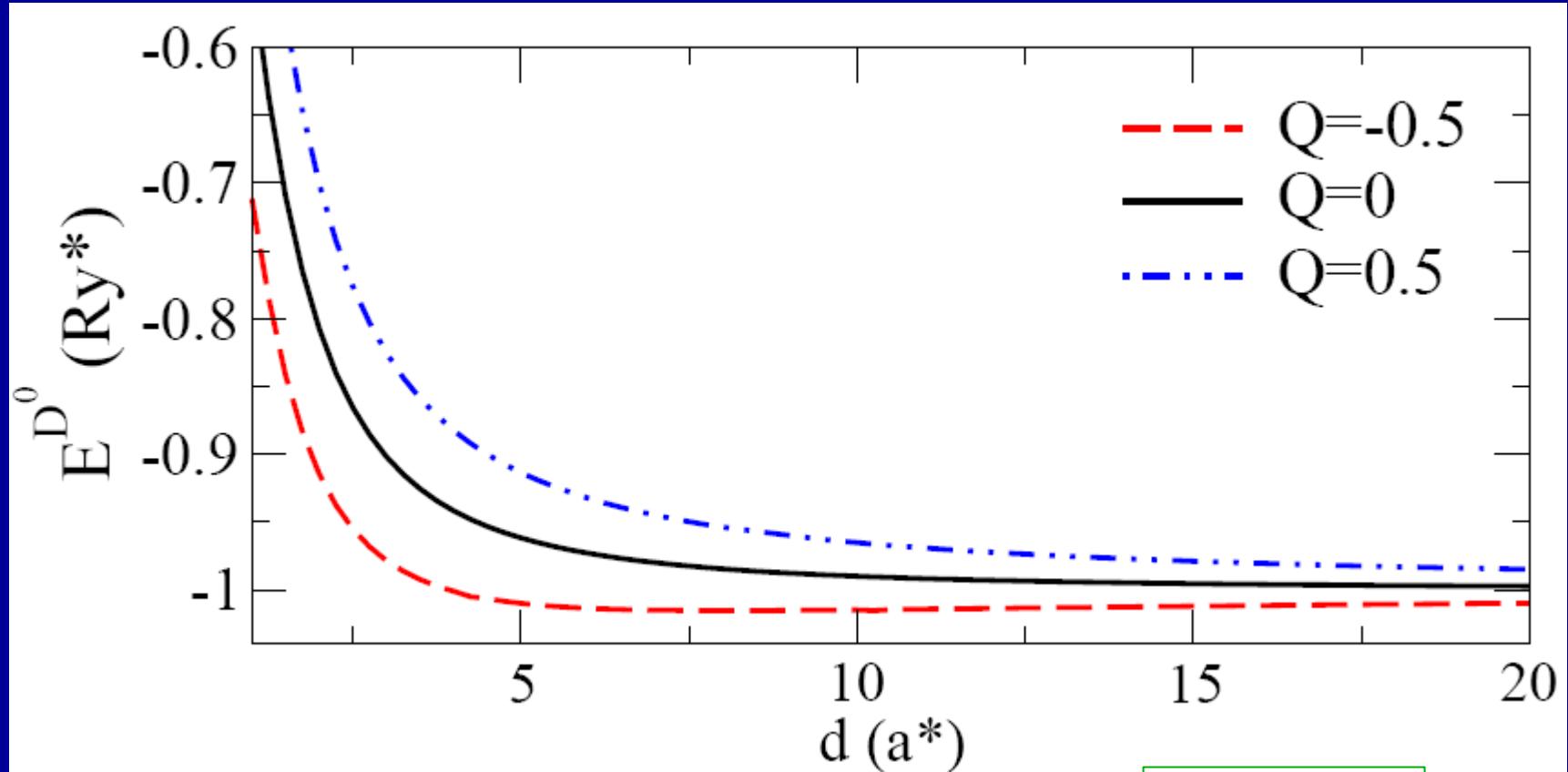
Boundary condition: $\Psi(z=-d)=0$ impenetrable barrier at $z=-d$

a, b and d In units of $a^* = 2.14 \text{ nm}$



$$\phi_{1s}(r, a) = \frac{1}{\sqrt{\pi a^3}} e^{-r/a} (z + d)$$

Results for a neutral donor (D^0)



$Q = -0.5 \rightarrow$ thick SiO_2 barrier

$Q = 0 \rightarrow$ no images

$Q = 0.5 \rightarrow$ effective Q for thin $\text{SiO}_2 +$ metal layer

$$Ry^* = 31.2 \text{ meV}$$
$$a^* = 2.14 \text{ nm}$$

Results for D⁻

$Q=-0.5 \rightarrow$ thick SiO₂ barrier

$$Ry^* = 31.2 \text{ meV}$$

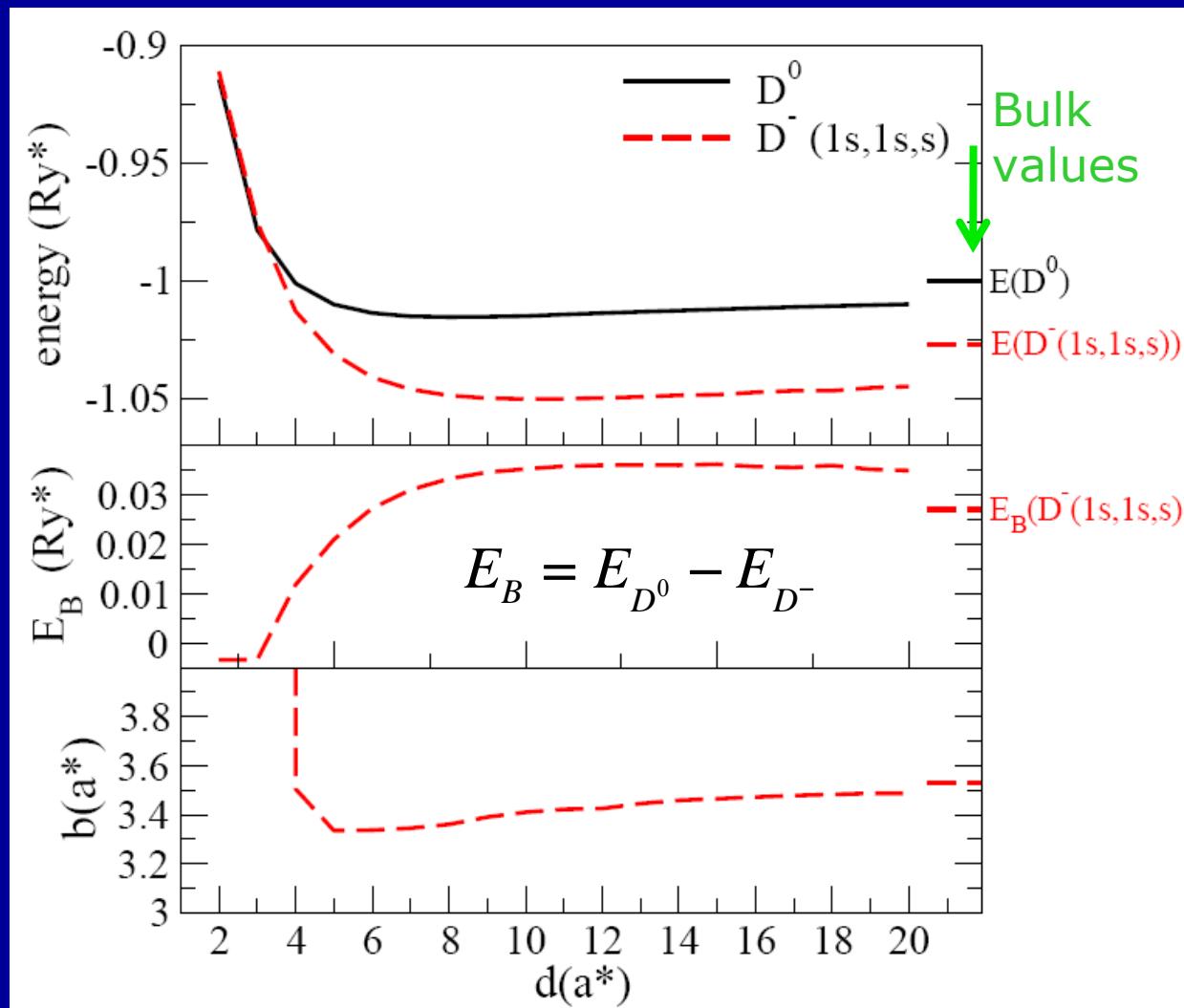
$$a^* = 2.14 \text{ nm}$$

- Bulk values are approached as d increases.

- D⁻ is not bound for $d < 4 a^*$. For small d the outer orbital radius b diverges.

- Binding energy is enhanced with respect to bulk for $d \geq 3 a^*$.

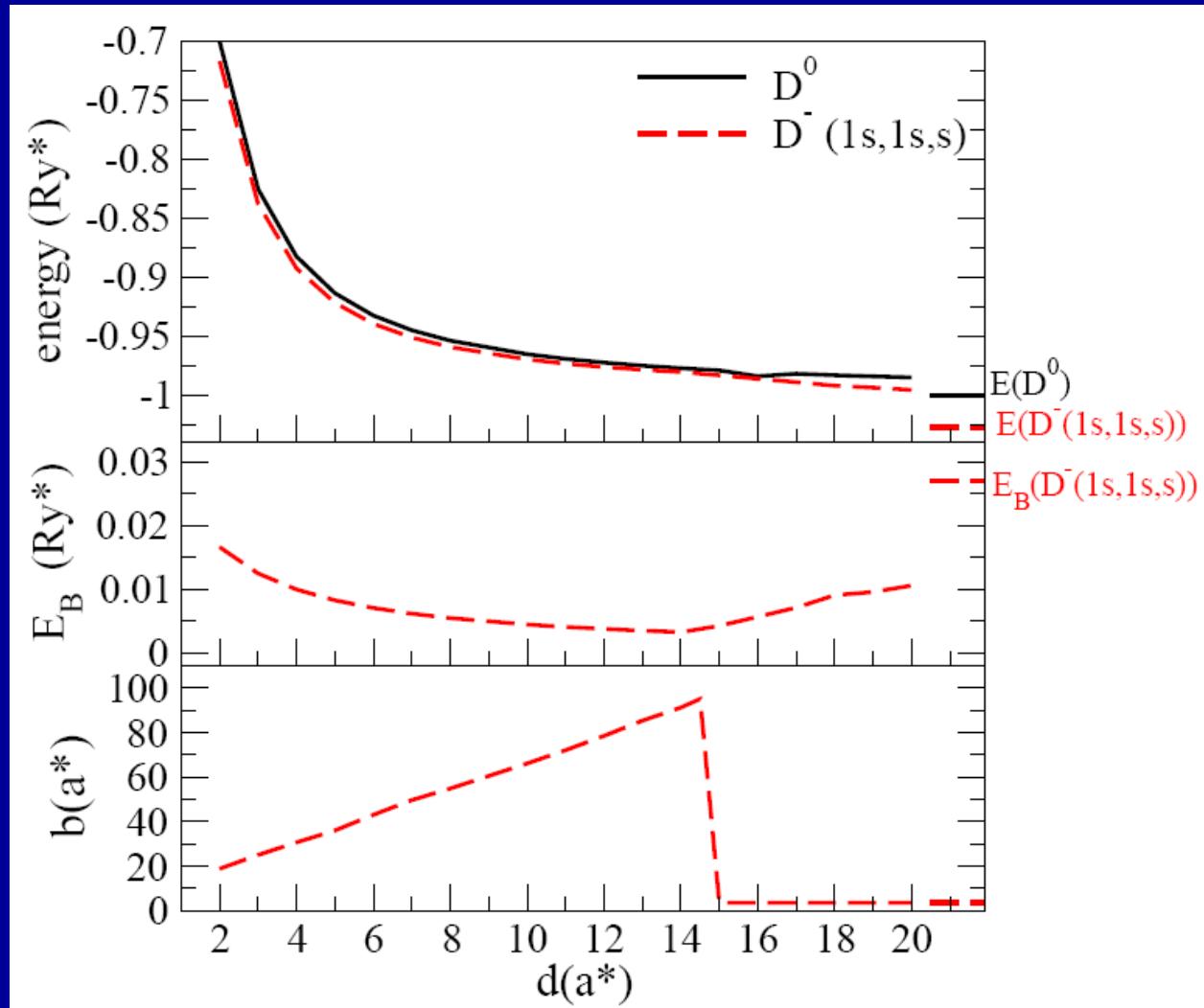
- Radius of inner orbital a similar to D⁰ at all d .



Results for D⁻

$Q=+0.5 \rightarrow \sim \text{thin SiO}_2 \text{ barrier} + \text{metal layer}$ $Ry^* = 31.2 \text{ meV}$
 $a^* = 2.14 \text{ nm}$

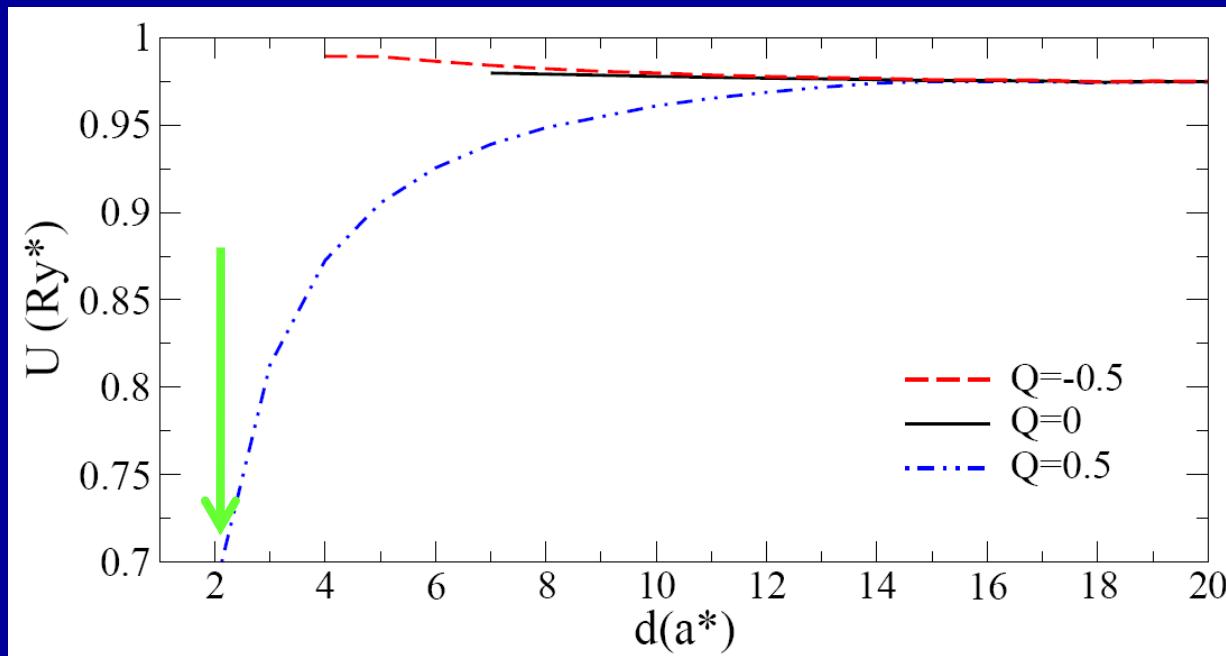
- Bulk values are approached as d increases.
- D⁻ is bound at all d (b is always finite).
- Binding energies are reduced with respect to bulk.



The combined effect of the insulator plus the metallic gate screening may be responsible for the observed reduction of U .

Charging energy for D⁻

Reminder: $U_{\text{bulk}} = 52 \text{ meV}$
 $U_{\text{FinFET}} = 28-36 \text{ meV}$  Ratio = 0.54-0.70



$Q=-0.5 \rightarrow$ thick SiO₂ barrier

$Q=0 \rightarrow$ no images

$Q=0.5 \rightarrow$ effective for thin SiO₂ + metal layer

$$U = E_{D^-} - 2E_{D^0}$$

Conclusions

- ✓ The energy spectrum of isolated donors in Si nanostructures differs from the bulk values. In particular, the charging energy of D^- charged donors is found to be smaller.
- ✓ We show that the proximity of metallic gates, separated from Si by a barrier material, modifies the binding energy of donors and, as a consequence, the charging energy for small distances between donor and interface is reduced.
- ✓ As a first approach to the problem, the combined effect of a barrier and metallic gates on nearby donor levels in Si is conveniently incorporated in a single dielectric mismatch parameter Q .

Collaborators

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Ministério da
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Relate work (D^0)

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